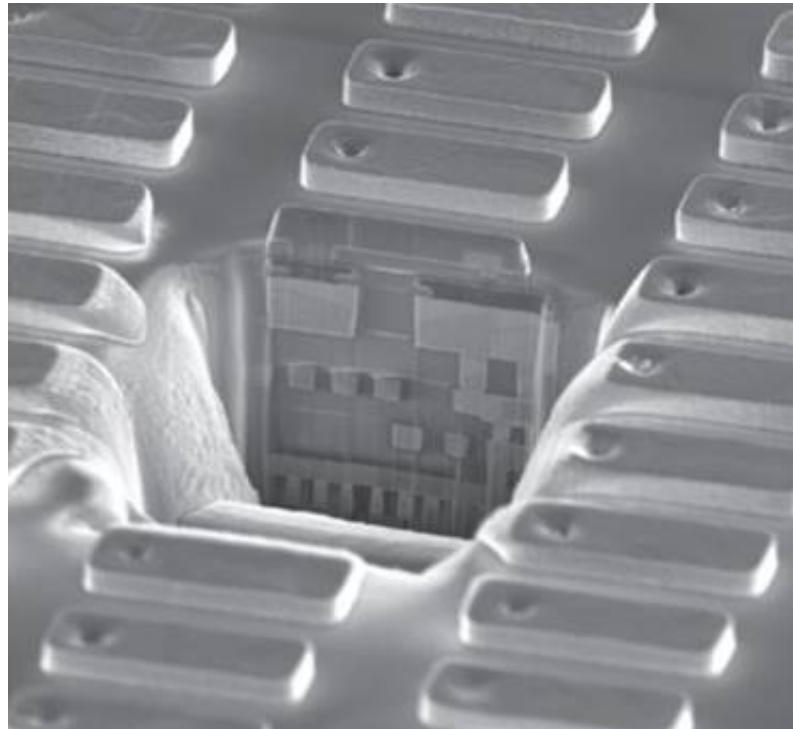


# A DEEP LOOK AT NEW MEMORIES



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**COUGHLIN ASSOCIATES & OBJECTIVE  
ANALYSIS**  
October 2024



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# CONTENTS

Contents .....	iii
Figures.....	1
Tables.....	6
Executive Summary .....	8
Introduction.....	10
Why Emerging Memories are Popular .....	15
Scaling Limits For Entrenched Technologies.....	15
3D NAND Flash Technologies.....	15
Future Flash Memories .....	19
3D DRAM.....	20
Embedded NOR and SRAM Scaling Challenges .....	22
Standalone NAND & DRAM Scaling Concerns.....	26
Technical Advantages.....	27
Emerging Memories for Radiation Tolerance .....	28
Alternatives to Using Emerging Memories .....	31
Potential Cost/GB Advantages .....	32
Which Applications want Emerging Memories First?.....	33
Current Emerging Memory Applications .....	34
Mass-Transit Fare Cards .....	34
Solid-State Drives (SSDs).....	35
Personal Fitness Monitors.....	36
Automotive .....	38
How a New Memory Layer Can Improve Computer Performance.....	41
How Persistence Changes the Memory/Storage Hierarchy .....	41
Changes in Computer Memory Usage.....	43
Standardizing The Persistent Memory Software Interface .....	45
Changing the DDR Standard for Persistence.....	46
Chiplets and UCIe.....	46
In-Memory Computing For AI .....	50
Fewer Constraints On MCU Programmers.....	51
Compute Express Link (CXL).....	52
The Crucial Importance Of The Economies Of Scale .....	55
How Scale Economies Undermined Intel’s “Optane” 3D XPoint PCM .....	58
Intel’s “Optane” 3D Crosspoint Memory Story.....	60
Optane Applications.....	61
Only Room for One at the Top .....	64
Understanding Bit Selectors .....	67
Crosspoint Arrays .....	75
All You Have To Do Is.....	79
Resistive RAM, ReRAM, RRAM, Memristor .....	81
ReRAM Device Function .....	82
Mott Devices.....	87
HPE’s Memristor .....	88

Stacking ReRAM Arrays .....	89
ReRAM CMOS Integration .....	91
3D NAND Approach to ReRAM.....	92
ReRAM and Artificial Intelligence.....	94
Current ReRAM Status .....	96
Ferroelectric RAM, FeRAM, FRAM.....	101
FRAM Operation .....	103
Ferroelectric Cell Structures .....	104
Capacitor-Based Cell .....	105
FTJ, the Ferroelectric Tunnel Junction .....	107
FRAM Product Status .....	107
Ferroelectric Materials: PZT, BST, and HfO.....	108
FRAM Device Characteristics .....	113
3D FeFET FRAM .....	115
Antiferroelectrics .....	117
The Future of FRAM .....	117
Phase Change Memory (PCM, PRAM, PCRAM).....	120
3D XPoint Memory: Intel's Optane.....	121
Operation of PCM.....	121
The OTS (Ovonic Threshold Switch) .....	125
PCM Advantages and Disadvantages .....	127
PCM Applications.....	128
MRAM (Magnetic RAM), STT MRAM (Spin Transfer Torque MRAM) .....	129
MRAM .....	129
The Eleven Basic MRAM Types.....	130
Toggle MRAM.....	132
STT MRAM.....	134
How STT Works .....	140
STT Manufacture .....	142
STT Strengths & Weaknesses.....	144
MRAM is Only SLC .....	146
Stacking MRAM.....	148
Spin-Orbit Torque MRAM .....	151
MeRAM, An Alternative Spin Memory Device.....	152
Spintronic Photonic Memory .....	154
Antiferromagnetic Memory (ATJ).....	155
Voltage Gated Spin Orbit Torque (VGSOT) .....	155
Racetrack Memory .....	155
Two MRAM "Trilemmas" .....	157
Is MRAM Sensitive to External Fields? .....	158
MRAM as a Substitute for SRAM Cache.....	159
MRAM in Artificial Intelligence .....	160
Other MRAM-Based Processors.....	162
Other MRAM Advancements .....	165
Current MRAM Status.....	165
Other Emerging Memory Types .....	167

Memcapacitor and Meminductor .....	167
Carbon Nanotubes (CNT) .....	168
Van der Walls CNT Flash.....	170
Polymeric Ferroelectric RAM (PFRAM) .....	170
III-V Floating Gate “UltraRAM”.....	171
Electrochemical RAM .....	173
Selector-Only Memory .....	173
Other Memory Types.....	174
Lithography.....	175
Multi-Patterning.....	175
Extreme UV (EUV) Technology .....	177
High Numerical Aperture EUV .....	179
EUV Challenges.....	181
Future Lithography .....	182
Nano-Imprint Lithography.....	182
3D Memory Circuit Design .....	187
3D Memory Circuit Approaches.....	189
Summary of Solid-State Memory & Storage Technologies .....	191
Current State of Discrete Emerging Memories.....	194
MRAM.....	194
ReRAM.....	195
FRAM .....	195
PCM .....	195
Current State of Embedded Emerging Memories.....	195
MRAM.....	195
ReRAM.....	195
FRAM .....	195
PCM .....	196
Emerging Memories and New Materials .....	197
Emerging Memory Process Equipment .....	198
MRAM and STT MRAM Process Equipment.....	200
Physical Vapor Deposition .....	204
Ion Beam and Plasma Etching .....	211
Photolithography (Patterning).....	221
Other Process Equipment.....	224
Device Testing .....	225
PCM, ReRAM, and OTS Manufacturing Equipment.....	230
Memory is Driving Semiconductor Capital Spending.....	232
Market Projections .....	235
Scenario Estimates .....	241
Estimates of Emerging Memory Capital Equipment Demand .....	249
Ion Beam Etching Equipment.....	250
Patterning Equipment.....	252
Magnetic Annealing Equipment .....	254
Physical Vapor Deposition Equipment.....	256
Test and Other Equipment .....	258

Summary of Emerging Memory Equipment Demand .....	261
Emerging Memory Manufacturing Support.....	265
Company Information.....	267
Memory And Applications Companies & Organizations.....	267
3D Plus.....	267
4DS Memory.....	267
Adesto Technologies.....	268
Advanced Memory Semiconductor (AMS) .....	268
Advanced Memory Technology (AMT) .....	268
Ambiq .....	268
Antaios .....	268
Arm .....	268
Atomera.....	269
Avalanche Technology .....	269
BAE Systems .....	270
BeSang .....	270
CAES .....	270
CAO-SIP .....	270
CEA-Leti.....	270
Celis Semiconductor .....	270
Cerfe Labs.....	271
Chinese Academy of Sciences (中国科学院) .....	271
Chiplus Semiconductor Corp. (晶发半导体股份有限公司) .....	271
CIES .....	271
Ciyu.....	271
CNSE (College of Nanoscale Science and Engineering) .....	271
Cobham-Aeroflex .....	272
Crocus Technology .....	272
CrossBar.....	272
Cypress.....	272
Dialog Semiconductor .....	272
eMemory Technology .....	273
Elpida .....	273
Eindhoven University of Technology (TU/e) .....	273
Ensurge Micropower.....	274
eVaderis .....	274
Everspin .....	274
Ferroelectric Memory Company (FMC).....	275
Fert Beijing Institute of Bei hang University.....	275
Frontgrade .....	275
Fujitsu Semiconductor .....	275
GigaDevice Semiconductor, Inc. (兆易创新) .....	276
Grandis.....	276
GREAT .....	276
Green Mountain Semiconductor .....	276

GreenWaves Technologies .....	277
Gyrfalcon Technology .....	277
Hikstor (驰拓科技) .....	277
HPE .....	277
Honeywell .....	277
Hynix .....	278
IBM .....	278
imec .....	278
Infineon .....	279
Innostar (昕原半导体) .....	279
Innovation Memory (新忆科技).....	279
Institute of Microelectronics (Chinese Academy of Sciences).....	280
Inston.....	280
Integrated Device Technology (IDT).....	280
Intel .....	280
Intermolecular .....	280
IntrinSic.....	281
ITRI.....	281
Jiangsu Advanced Memory (江苏时代芯存半导体) .....	281
Kepler Computing.....	281
Kioxia.....	281
Knowm.....	282
Leti .....	282
Macronix .....	282
MagSil.....	283
Magtera .....	283
Merck .....	283
Microchip .....	283
Micron Technology .....	283
Microsemi .....	284
Micross.....	284
NaMLab .....	284
Nantero.....	284
National Tsing Hua University .....	284
NEC.....	285
Netsol .....	285
Nextorage.....	285
Numem.....	285
Numonyx.....	286
Nuvoton.....	286
NVE .....	286
NXP .....	286
Ovonyx.....	286
Panasonic .....	286

QuInAs Technology .....	287
Qualcomm .....	287
Rambus .....	287
Ramtron .....	287
Reliance Memory (合肥睿科微电子有限公司) .....	287
Renesas Electronics .....	288
ROHM .....	288
Samsung Semiconductor .....	289
SanDisk .....	289
Seagate Technology .....	289
Semron, GmbH .....	290
Shanghai Ciyu Information Technologies (SCIT, 上海磁宇/磁宇信息) .....	290
SiEn (QingDao) Integrated Circuits (芯恩(青岛)集成电路) .....	290
Silicon Magnetic Systems .....	290
SK hynix .....	291
Sony Corporation .....	291
Spin-Ion .....	291
Spin Memory .....	291
Spingate Technology .....	292
SPINTEC .....	292
Spin Orbitronics .....	292
SRAM & MRAM Group .....	292
Stanford University .....	293
STMicroelectronics .....	293
Sunrise Memory .....	293
SUNY (State University of New York) .....	293
sureCore .....	293
Symetrix .....	294
TDK .....	294
Teledyne e2v Semiconductors .....	294
TetraMem .....	294
Texas Instruments .....	294
TMC .....	295
Tohoku University .....	295
Toshiba .....	295
Truth Memory Tech, Corp (TMC, 致真存储) .....	295
TU/e .....	295
University at Albany College of Nanoscale Science and Engineering (CNSE) ....	295
Unidym .....	295
Veevx .....	296
Weabit Nano .....	296
Western Digital .....	296
Winbond .....	297
XTX Technology (芯天下) .....	297
Semiconductor Foundries .....	297

Crocus Nanoelectronics .....	297
DB HiTek.....	297
GlobalFoundries.....	298
Hangzhou HFC Semiconductor (杭州积海半导体有限公司) .....	298
Lapis Semiconductor .....	298
Samsung.....	299
SilTerra .....	299
SkyWater Technology .....	299
SMIC (中芯) .....	299
Tower Semiconductor.....	299
TPSCo .....	300
TSMC.....	300
UMC - United Microelectronics Corporation.....	300
Capital Equipment Manufacturers .....	301
Accretech .....	301
ANELVA .....	301
Applied Materials.....	301
ASM .....	301
ASML .....	301
Bruker .....	302
Canon .....	302
Canon-ANELVA .....	302
CAPRES A/S .....	302
Hitachi High Technology.....	302
Hprobe.....	303
Integral Solutions, Inc. (ISI) .....	303
Jusung Engineering .....	303
Keysight Technologies.....	303
KLA Tencor.....	303
Lake Shore .....	304
Lam Research.....	304
Leuven Instruments (鲁汶仪器) .....	304
MagOasis .....	304
MicroSense .....	304
Nanomagnetics Instruments.....	305
Neoark.....	305
Nikon.....	305
Onto Innovation .....	305
Oxford Instruments .....	305
Plasma Therm .....	305
SHB.....	306
Singulus Technologies .....	306
Smart Tip .....	306
Tokyo Electron.....	306
Tokyo Seimitsu .....	306

Ulvac .....	306
Veeco .....	306
Methodology .....	307
Further Reading .....	308
Authors.....	309
Tom Coughlin .....	309
Jim Handy .....	309

# FIGURES

Figure 1. Memory Density and Power Requirements by Application Category .....	10
Figure 2. Solid State Memory/Storage Technologies .....	11
Figure 3. Rough Comparison of Established and Emerging Memory Types .....	12
Figure 4. 3D NAND Flash Memory Topology.....	16
Figure 5. Toshiba's BiCS and Samsung's TCAT 3D NAND Structures .....	17
Figure 6. Cost of Transition from One NAND Manufacturing Process to the Next .....	18
Figure 7. NAND Flash Chip Technology Roadmap.....	20
Figure 8. Intel's Antiferroelectric DRAM.....	21
Figure 9. SRAM Cell Sizes Shrink More Slowly Than Processes, Causing $f^2$ to Balloon .....	23
Figure 10. Historically, SRAM Caches Scaled in Proportion to Processor Logic .....	24
Figure 11. SRAM in Future Processes Will Scale More Slowly than Processor Logic ..	25
Figure 12. SRAM Cell Size vs. Process for Intel, Samsung, and TSMC .....	26
Figure 13. Cross Section of a Flash Memory Bit Cell.....	29
Figure 14. An Alpha Particle Drags Electrons Out of the Floating Gate .....	30
Figure 15. Infineon's Vision of Future External Flash Topologies .....	31
Figure 16. Guangzhudong Shenzen Railway Company Fare Card .....	34
Figure 17. IBM Flashcore Module Manufactured with Flash and MRAM Storage.....	35
Figure 18. Mangstor MX6300 NVMe SSD with Everspin MRAM cache (circled) .....	36
Figure 19. Google's Fitbit Luxe .....	37
Figure 20. Garmin's Versa 4 .....	37
Figure 21. Garmin Fenix 7 Pro – Solar Edition .....	38
Figure 22. Lucid Air Grand Touring Automobile .....	39
Figure 23. Rimac Nevera Electric Sports Car.....	39
Figure 24. BMW 1000 RR Motorrad Motorsport Super Bike.....	40
Figure 25. Memory/Storage Price per Gigabyte vs. Performance .....	42
Figure 26. Progression of Storage Technologies with Nonvolatile Solid-State Storage ..	44
Figure 27. Solid-State Storage Latency Sources.....	45
Figure 28. Gordon Moore's Estimation of Contributions from Transistor Dimensions, Die Size, and Circuit Cleverness .....	47
Figure 29. Die Sizes Over Time .....	48
Figure 30. AMD EPYC 7702 with I/O Chiplet Surrounded by Eight Core Complex Chiplets .....	49
Figure 31. ReRAM System on Chip .....	51
Figure 32. Intel's DDR-T Interface .....	53
Figure 33. Large CXL-Based System with Eight Hosts Sharing Two Memory Pools....	54
Figure 34. NAND Flash Prices Crossed Below DRAM in 2004.....	56
Figure 35. 2004 NAND Gigabyte Shipments Reached 1/3rd That of DRAM .....	57
Figure 36. Estimated Intel 3D XPoint Quarterly Losses .....	59
Figure 37. Estimated Optane Revenues and Petabyte Shipments.....	60
Figure 38. Intel's View of the Memory-Storage Hierarchy .....	62
Figure 39. Redis Virtual Machine Count vs. Memory Size.....	63

Figure 40. Emerging Memory Competitive Battle .....	65
Figure 41. Bit Selectors - 3-Terminal (Left) 2-Terminal (Right) .....	68
Figure 42. Overhead View of a Simple Crosspoint Array.....	69
Figure 43. Reading When One Bit Is in a Low-Resistance State .....	69
Figure 44. Sneak Paths Occur when Multiple Bits are in a Low Resistance State.....	70
Figure 45. Space Penalty of a 3-Terminal Selector .....	71
Figure 46. Bidirectional Diode Selector .....	72
Figure 47. A 1TnR Selector Configuration.....	73
Figure 48. 3D Crosspoint Array Stacking.....	75
Figure 49. Stacked Crosspoint Memory Array .....	76
Figure 50. Bit Cost as a Function of Layer Count - Crosspoint 3D Memory .....	77
Figure 51. Bit Cost as a Function of Layer Count - 3D NAND Approach.....	78
Figure 52. ReRAM Filament Cell Conduction and Switching .....	82
Figure 53. ReRAM Scaling.....	83
Figure 54. ReRAM Resistance Scaling .....	83
Figure 55. TaOx ReRAM Device .....	84
Figure 56. TaOx Oxygen Vacancy Structure of eMemory Cell .....	85
Figure 57. Current Levels and Voltages for ReRAM Switching.....	85
Figure 58. Cross-section Photo of Weebit Nano ReRAM.....	86
Figure 59. CeRAM Cell vs. ReRAM Cell .....	87
Figure 60. Where the Memristor Fits in the World of Passive Components .....	88
Figure 61. Cross Section of HPE's Memristor Structure .....	89
Figure 62. ReRAM Stacked Crosspoint Array .....	90
Figure 63. ReRAM CMOS Integration.....	91
Figure 64. Two-Mask ReRAM Element in Tungsten Vias .....	92
Figure 65. Cross-Section SEM of 8-Layer 3D ReRAM .....	93
Figure 66. 3D ReRAM Structure/Process.....	93
Figure 67. A Simplified View of a Neural Network.....	94
Figure 68. I/V Curve of Weebit Nano ReRAM .....	97
Figure 69. MCU with Weebit ReRAM.....	98
Figure 70. TetraMem's MX100 Analog Neural Network Chip, Based on ReRAM .....	99
Figure 71. Microphotograph of Intrinsic's ReRAM Array .....	100
Figure 72. Early Ferroelectric Memory - 1955 Bell Labs 256-Bit Device .....	102
Figure 73. Hysteresis Curve of Ferroelectric Memory .....	103
Figure 74. FRAM Perovskite Displacement .....	104
Figure 75. Topology of FRAM, FeFET, and Ferroelectric Tunnel Junction.....	105
Figure 76. FeFET Cross Section.....	106
Figure 77. FeFET Transistor.....	106
Figure 78. Micron's 32Gb Ferroelectric NVDRAM .....	109
Figure 79. SEM Photo of Micron's Stackable Ferroelectric NVDRAM .....	109
Figure 80. Publication Count for FeFET Research Papers .....	110
Figure 81. Amorphous, Crystalline, and Ferroelectric Hafnium Oxide .....	111
Figure 82. Typical Dimensions of PZT and HfO Capacitors .....	112
Figure 83. Memory Properties of Ferroelectric Hafnium Oxide .....	113
Figure 84. FRAM Planar Cell Structure .....	115
Figure 85. 3D Hafnium Oxide FRAM Built Using 3D NAND Techniques .....	116

Figure 86. Antiferroelectric Hysteresis Loop .....	117
Figure 87. SK hynix' Ferroelectric 3D NAND flash .....	119
Figure 88. Crosspoint Memory Using PCM Cells.....	122
Figure 89. Characteristics of the Read, Write and Erase Cycle for PCM Materials.....	123
Figure 90. PCM Memory Cell .....	124
Figure 91. Cross Section of PCM Cell .....	124
Figure 92. STMicroelectronics' Transistor-Selected PCM Cell .....	125
Figure 93. Hysteresis in an Ovonic Threshold Switch .....	126
Figure 94. Comparing the Thickness of a Conventional PCM Cell to an OTS-Only Cell .....	127
Figure 95. Basic Cell Diagram for Toggle MRAM.....	133
Figure 96. Toggle MRAM Architecture .....	134
Figure 97. Die Photograph of Everspin 1Gb STT MRAM.....	135
Figure 98. GlobalFoundries' Roadmap for Embedded MRAM .....	136
Figure 99. Samsung's MRAM In-Memory Processing 64X64 array Device.....	138
Figure 100. TSMC's Embedded MRAM/RRAM Plans .....	139
Figure 101. Parallel to Antiparallel Switching .....	141
Figure 102. Spin Transfer Torque Operation.....	141
Figure 103. In-Plane and Perpendicular Magnetic Tunnel Cells .....	142
Figure 104. STT MRAM Cell Structure .....	142
Figure 105. Everspin STT MRAM Stack Structure.....	143
Figure 106. Everspin STT MRAM Produced on 28nm GlobalFoundries Process.....	144
Figure 107. SEM Photo of 1S1M MRAM cross Section Presented by SK hynix and Kioxia.....	145
Figure 108. Comparing NOR vs. STT MRAM Write Energy.....	146
Figure 109. STT MRAM Current Operation .....	147
Figure 110. Reading a Multi-Bit MRAM Cell.....	147
Figure 111. DRAM, NAND Flash and STT MRAM Price vs. Latency.....	148
Figure 112. STT MRAM Cross Section .....	149
Figure 113. Bit Dimensions of Ideal MRAM, DRAM, Planar NAND Flash and HDD	149
Figure 114. STT MRAM Embedded Memory .....	150
Figure 115. STT-MRAM vs. SOT-MRAM .....	151
Figure 116. MeRAM Device Structure.....	153
Figure 117. MeRAM Stack.....	153
Figure 118. IBM's Racetrack Memory - Conceptual Diagram .....	156
Figure 119. Laboratory Embodiment of IBM's Racetrack Memory.....	157
Figure 120. Spin Memory's MRAM "Tug of War" .....	157
Figure 121. Alif Semiconductor MRAM-Based MCU.....	161
Figure 122. Numem DNN Device with MRAM for Space Applications .....	162
Figure 123. Ambiq Apollo 4 IoT SoC .....	163
Figure 124. Ambiq Apollo 4 Blue 16Mb Memory Array in a Fitbit Luxe Fitness Band .....	163
Figure 125. Sony eMRAM Buffer Memory for CIS .....	164
Figure 126. The Memcapacitor and Meminductor Added to Chua's Memristor Diagram .....	167
Figure 127. Semron's Memcapacitor .....	168

Figure 128. CNT Fabric.....	169
Figure 129. PFRAM 3-Layer Polymeric Memory.....	171
Figure 130. Profile of University of Lancaster UltraRAM bit cell.....	172
Figure 131. Electrochemical RAM Bit Cell Cross-Section .....	173
Figure 132. Original Single-Patterned Features.....	176
Figure 133. Clad the Sides of the Original Pattern .....	176
Figure 134. Remove the Original Pattern. The Remaining Cladding is a Doubled Pattern .....	176
Figure 135. Clad the Sides of the Doubled Pattern.....	177
Figure 136. Remove the Doubled Pattern. The Remaining Cladding is the Quadrupled Pattern .....	177
Figure 137. Light Spectrum .....	178
Figure 138. EUV Scanning Lithographic Exposure System .....	178
Figure 139. imec/ASML hNA EUV Roadmap.....	180
Figure 140. ASML hNA EUV Beam Path.....	181
Figure 141. Nanoimprint Process .....	184
Figure 142. Nanoimprint Depressions .....	185
Figure 143. Fluid Dispense Process.....	185
Figure 144. Largest Memory Densities Presented at IEEE Research Conferences, 2001-2022.....	192
Figure 145. Future Memory/Storage Hierarchy.....	194
Figure 146. Elements Used in New Memories .....	197
Figure 147. Emerging Memory Cell Structure Comparison.....	198
Figure 148. MRAM Memory Cell .....	201
Figure 149. MRAM Cross-Section .....	202
Figure 150. MRAM Manufacturing Process Flow .....	202
Figure 151. Key MRAM Process Equipment .....	203
Figure 152. Applied Materials CMP System.....	205
Figure 153. Applied Materials Endura Clover Platform.....	206
Figure 154. Canon Anelva EC7800 PVD Tool .....	207
Figure 155. Canon Anelva NC7900 PVD Tool .....	207
Figure 156. Singulus Timaris II PVD Cluster Tool Platform.....	208
Figure 157. Singulus PVD Cluster Tool Platforms .....	208
Figure 158. Tokyo Electron Exim PVD Cluster Tool Platform .....	209
Figure 159. Ulvac ENRON EX W300 Multilayer Thin Film Deposition System .....	210
Figure 160. Veeco Nexus IBD Ion Beam Deposition System.....	211
Figure 161. A Three Grid Ion Beam Extraction System .....	212
Figure 162. MTJ Etching Process.....	212
Figure 163. Applied Materials Centura .....	213
Figure 164. Canon Anelva Nc8000 Ion Beam Etch Machine .....	214
Figure 165. Hitachi High Technology E-600/8000 Nonvolatile Etch System .....	215
Figure 166. Lam Research Semiverse .....	217
Figure 167. Lam Research Kiyo Ion Beam Etching Chamber .....	217
Figure 168. Oxford Instruments Ionfab 300 IBE System.....	218
Figure 169. Plasma Therm QuaZar Ion Beam Etch and Deposition System.....	219
Figure 170. Ulvac NE-7800H Non-Volatile Material Etching Tool .....	220

Figure 171. Veeco Nexus IBE-420I Ion Beam Etching System.....	220
Figure 172. ASML Deep UV Photolithography Tool .....	222
Figure 173. Nikon Photolithographic Product Lines .....	222
Figure 174. Canon Lithographic Stepper Products.....	223
Figure 175. Tokyo Electron MRT300 Magnetic Annealing Tool .....	224
Figure 176. HProbe 3D High Magnetic Field Wafer Probe .....	226
Figure 177. Keysight Technology NX5730A MRAM Test Platform .....	227
Figure 178. MicroSense (KLA/Tencor) Polar Kerr System for Perpendicular STT MRAM.....	228
Figure 179. Atomic Force Microscopy Concept (AFM) .....	229
Figure 180. Applied Materials Endura Impulse for PCM and ReRAM .....	231
Figure 181. SEMI's Total Semiconductor Wafer Capacity History and Forecast .....	232
Figure 182. Standalone Memory Prices 2023-2034 .....	236
Figure 183. Standalone Memory Annual Petabyte Shipments, 2023-2034.....	238
Figure 184. Standalone Memory Annual Revenues 2023-2034.....	240
Figure 185. Three Scenarios for Standalone Emerging Memory Annual Wafer Consumption 2023-2034.....	242
Figure 186. Three Scenarios for Embedded Emerging Memory Annual Wafer Consumption 2023-2034.....	243
Figure 187. Three Scenarios for Combined Emerging Memory (Stand-Alone and Embedded) Annual Wafer Consumption 2023-2034 .....	245
Figure 188. Three Scenarios for Combined Emerging Memory Petabyte Production 2023-2034 .....	246
Figure 189. Three Scenarios for Combined Emerging Memory Revenues 2023-2034	247
Figure 190. Capital Equipment Estimate Process Flow.....	250
Figure 191. Three Scenarios of MRAM Ion Beam Etching Equipment Spending 2023- 2034.....	252
Figure 192. Three Scenarios of Emerging Memory Patterning Equipment Spending 2023-2034 .....	254
Figure 193. Three Scenarios of MRAM Magnetic Annealing Equipment Spending 2023- 2034.....	256
Figure 194. Three Scenarios of Emerging Memory Physical Vapor Deposition Equipment Spending 2023-2034.....	258
Figure 195. Combined Test and Other Equipment Baseline Spending Estimates 2023- 2034.....	260
Figure 196. Three Scenarios of Test and Other Equipment Spending 2023-2034 .....	261
Figure 197. Emerging Memory Combined Baseline Equipment Spending Estimates 2023-2034 .....	263
Figure 198. Three Scenarios of Total Equipment Spending 2023-2034 .....	264

# TABLES

Table 1. Solid State Memory Technology Comparison.....	43
Table 2. UCIE Key Members .....	50
Table 3. DRAM and SLC NAND Die Sizes.....	55
Table 4. MRAM Suitability for Cache .....	160
Table 5. Cell Sizes for Ambiq NOR Flash and MRAM .....	164
Table 6. Cell Size Comparison of Production MRAM Cell Sizes.....	165
Table 7. Summary of Emerging Memory Technologies .....	193
Table 8. MRAM Process Equipment Vendors .....	204
Table 9. Tokyo Electron Magnetic Annealing Product Line-Up.....	225
Table 10. Historical Equipment Spending by Region (\$B) .....	233
Table 11. Standalone Memory Prices, 2023-2034 (\$/GB) .....	236
Table 12. Standalone Memory Annual Petabyte Shipments, 2023-2034 .....	237
Table 13. Assumptions for Baseline Standalone Emerging Memory Model, Based on MRAM.....	239
Table 14. Standalone Memory Annual Revenues 2023-2034 (\$M).....	240
Table 15. Three Scenarios for Standalone Emerging Memory Annual Wafer Consumption 2023-2034.....	241
Table 16. Three Scenarios for Embedded Emerging Memory Annual Wafer Consumption 2023-2034.....	243
Table 17. Three Scenarios for Combined Emerging Memory (Stand-Alone and Embedded) Annual Wafer Consumption (Units) 2023-2034 .....	244
Table 18. Three Scenarios for Combined Emerging Memory Production 2023-2034 (Petabytes).....	246
Table 19. Three Scenarios for Combined Emerging Memory Revenues 2023-2034 (\$M) .....	247
Table 20. MRAM Ion Beam Etching Equipment Baseline Unit Shipment Estimates 2023-2034 .....	251
Table 21. MRAM Ion Beam Etching Equipment Baseline Spending Estimates 2023- 2034 (\$M) .....	251
Table 22. Emerging Memory Patterning Equipment Baseline Unit Shipment Estimates 2023-2034 .....	253
Table 23. Emerging Memory Patterning Equipment Baseline Spending Estimates 2023- 2034 (\$M) .....	253
Table 24. MRAM Magnetic Annealing Equipment Baseline Unit Shipment Estimates 2023-2034 .....	255
Table 25. MRAM Magnetic Annealing Equipment Baseline Spending Estimates 2023- 2034.....	255
Table 26. Emerging Memory Physical Vapor Deposition Equipment Baseline Unit Shipment Estimates 2023-2034 .....	257
Table 27. Emerging Memory Physical Vapor Deposition Equipment Baseline Spending Estimates 2023-2034.....	257
Table 28. Test and Other Equipment Baseline Unit Shipment Estimates 2023-2034 (\$M) .....	258

Table 29. Test & Other Equipment Price Estimates 2023-2034.....	259
Table 30. Test & Other Equipment Baseline Spending Estimates 2023-2034 .....	259
Table 31. Combined Equipment Baseline Unit Shipment Estimates 2023-2034 .....	262
Table 32. Combined Equipment Baseline Spending Estimates 2023-2034 (\$M) .....	262
Table 33. Emerging Memory Foundry Offerings.....	265
Table 34. Sellers of Emerging Memory Based Chips.....	266

# EXECUTIVE SUMMARY

Scaling limits have become very real for flash memory (NAND and NOR), DRAM, SRAM, and other popular memory technologies are facing technology limits to their continued improvement. With this facing them, many researchers are devoting significant resources to develop new memory technologies. The most promising of these new technologies are nonvolatile memories, which can be used for long-term storage or to provide a memory that retains information when powered down. Nonvolatile memories offer energy savings that are appealing to designers of battery and ambient powered devices and also for energy savings, and performance improvements in data centers.

This report covers PCM, ReRAM, FRAM, Toggle MRAM, and STT MRAM, as well as a variety of less mainstream technologies such as III-V devices and carbon nanotubes. At the moment, resistive RAM (ReRAM) technologies are viewed as a potential replacement for flash memory, but future NAND flash memory is anticipated to support several more layer-count increases and other approaches for higher storage density, to push costs much lower than today, allowing many years to pass before a replacement is required. Thus, a transition from NAND flash to some other technology is not expected to occur until the next decade, at the earliest.

In this market, the economies of scale reign supreme. We saw that with Intel's 2022 termination of its Optane 3D XPoint campaign and had seen the same phenomenon play out before with NAND flash, whose high volume drove its costs below that of DRAM. The report delves deeply into the impact of the economies of scale, and concludes that both the success of NAND flash and the failure of Optane proved that wafer volume must approach 10% of the volume of a competing technology in order to reach cost parity.

Embedded NOR flash has become the first technology to convert in significant volume to an emerging memory technology, yielding to toggle-mode magnetic RAM (MRAM) and spin transfer torque RAM (STT MRAM), and in some cases SRAM is also being replaced with MRAM. Within the foreseeable future an emerging technology could displace some DRAM, well before ReRAM replaces NAND flash memory.

The rate of emerging memory technology development and increasing production volume will gradually result in lower prices, and low prices are the single most important driver to the acceptance of a new memory technology. Systems architects are interested in replacing volatile memory with high-speed, high-endurance nonvolatile memory and that bolsters the popularity these technologies will gain as their volume increases to reduce production costs (and thus purchase prices).

Ferroelectric RAM (FRAM) and some ReRAM technologies already ship to certain niche applications, despite the use of materials that are poorly managed in a production environment. HfO FRAM offers promise by using a material that is well-understood in today's FinFET fabs, and this might allow the number of niche markets available for FRAM to increase.

These new memory types enable new system configurations that have so far been unavailable. A nonvolatile main memory and cache memory in a computer will reduce power usage directly as well as enable new power saving modes, provide faster recovery

from power off, and enable more stable computer architectures that retain their state even when power is off. Spintronic technology, that uses spin rather than current for logic functions, could be used to make future microprocessors. A combination of spin-based logic and spin-based memory would be only natural on a single wafer, and could team up to enable very efficient in-memory computing. Many of the emerging memory technologies profiled in this report are being used as the basis of neuromorphic computing chips, which may become the basis for future AI-enabled endpoint devices.

The first widespread use of emerging memories is for embedded memory on a CMOS logic chip, replacing NOR flash, which has reached its scaling limit at 28nm, and is today frequently being replaced with MRAM and ReRAM. Single-transistor MRAM cells are now competing with multi-transistor SRAM, to dramatically reduce the number of memory transistors on a chip in order to provide a lower-cost, higher-density solution. Several enterprise and consumer devices currently use MRAM as an embedded memory, and this trend will continue.

MRAM processes have already been developed on conventional CMOS logic processes, allowing them to be built directly on top of CMOS logic wafers, using fewer additional mask steps than a more conventional flash memory. The use of a nonvolatile emerging memory can provide significant power savings in comparison to SRAM. As emerging memory cost per gigabyte (\$/GB) approaches that of SRAM, this replacement could lead to significant market expansion.

It is projected that total baseline emerging memory annual shipping capacity will rise from an estimated 340TB in 2023 to 8.46EB in 2034. Total emerging memory baseline revenues are expected to increase from \$421M in 2023 to about \$71.7B by 2034. The bulk of this rapid revenue growth will be supported by emerging memories' displacement of SRAM, NOR flash and some DRAM.

Emerging memory demand should drive incremental demand for the capital equipment needed to manufacture these devices. This report models this requirement by focusing on the MRAM market. While MRAM can be built on standard CMOS circuits supplied by large semiconductor fabricators, specialized fabrication equipment is required for the MRAM layers. This additional equipment is similar to or the same as that used in manufacturing the magnetic read sensors in hard disk drives. Other emerging memory technologies will require their own complement of additional equipment, most of it identical to tools that are already in widespread use.

Growing demand for emerging memory technologies will increase total manufacturing equipment revenues by an estimated \$53.4M in 2023 to between \$434M to \$3.8B by 2034 with a baseline projected spending of \$2.4B.

# INTRODUCTION

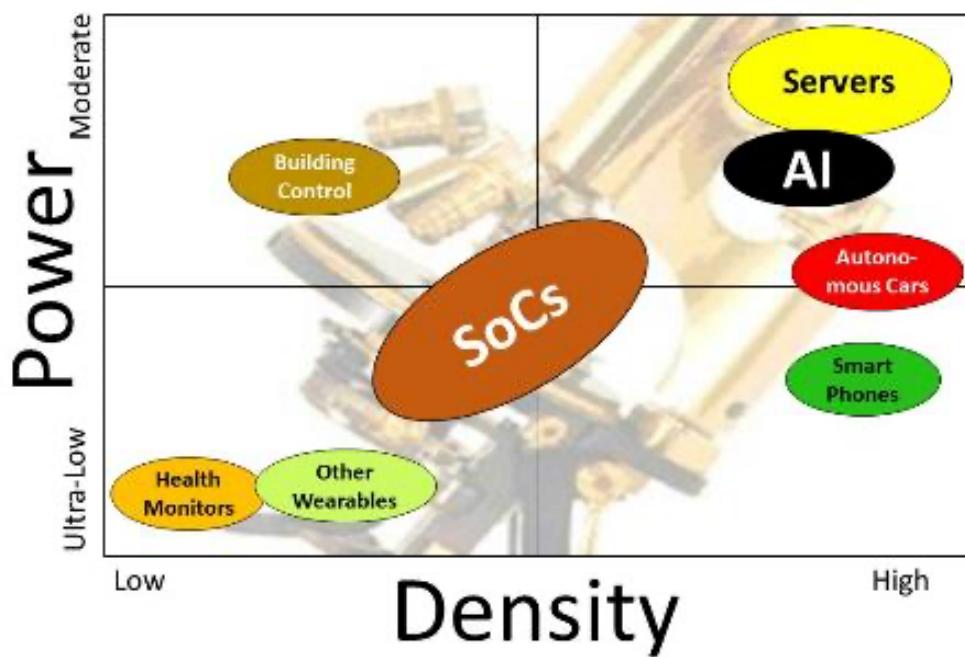
As the Internet of Things builds out, and as a growing number of devices make new measurements of data that was previously unmeasured, the world's data processing needs will grow exponentially.

This growth will not be matched with increases in communication bandwidth, despite the adoption of new wireless standards like 5G. In response to this mismatch, an increasing amount of processing will be performed at the edge, particularly in single-chip devices whose power consumption must be kept in check. This is the application that promises to benefit the most from today's nascent adoption of emerging memory technologies.

IoT endpoints need to process and interpret this data, often in near real time. Combine this with the amount of data that must be stored and processed to train various types of artificial intelligence (AI) models, and the result is a great increase in demand for memory and storage.

Figure 1 provides a rough idea of the memory density and power consumption needs of a number of modern application types.

**Figure 1. Memory Density and Power Requirements by Application Category**



Source: Objective Analysis, 2018

In order to make this information useful, our ability to process and interpret this data must also increase—the use of fast nonvolatile memory devices will be a key element in making this vast amount of information useful. Improved processing performance requires a good match of processor speed with communication bus speeds as well as memory data rates. It also requires latencies that are adequate for the application being processed.

More advanced semiconductor processing technologies will also play a key role in the transition to emerging memories, as established memory technologies like NOR flash and SRAM fail to keep pace with the relentless march of Moore's Law.

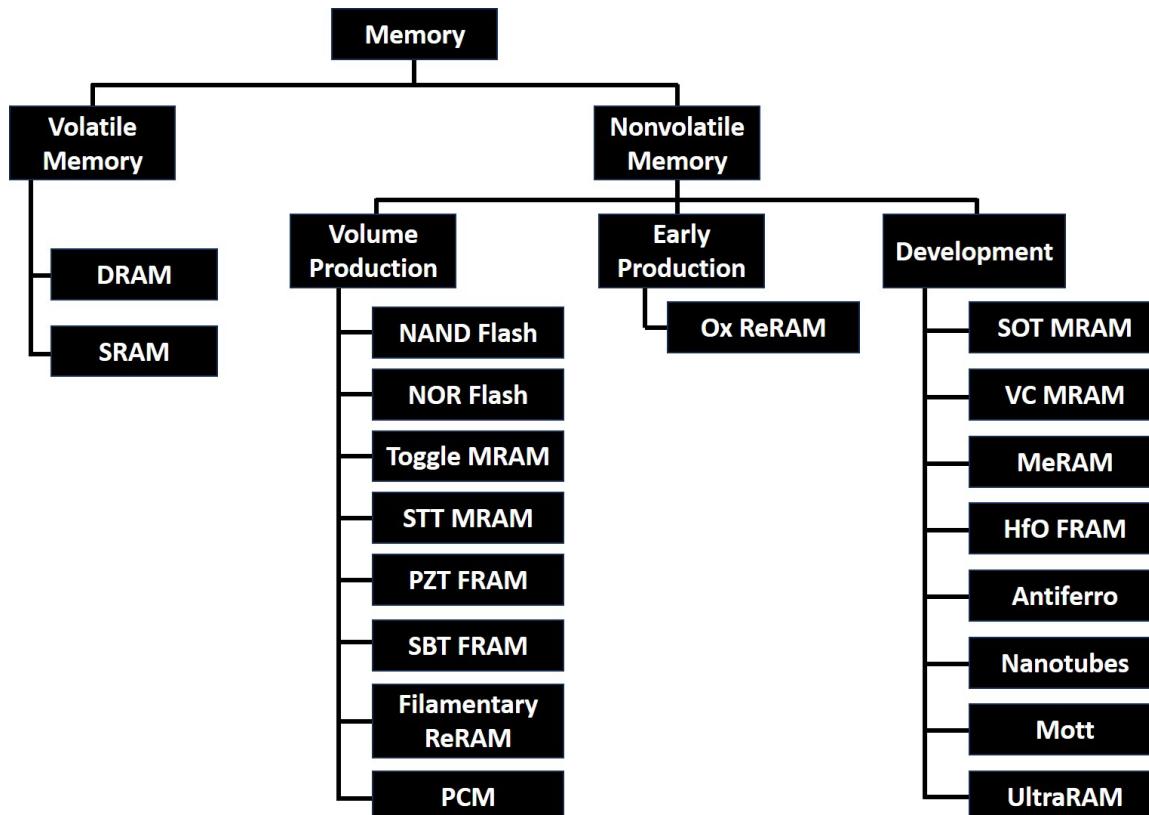
This report investigates the technologies associated with solid-state nonvolatile memories and evaluates each from the viewpoint of competition with current volatile memories, magnetic hard disk drives and flash memories.

There are numerous emerging solid-state nonvolatile memory technologies described in the literature, some rather old, while others are more recent. Some products such as ferroelectric random-access memory (FRAM), phase change RAM (PCM) and toggle and STT magnetic RAM (MRAM) are available as low to moderate density memory or storage products. Other technologies including spin-orbit torque MRAM and resistive RAM (ReRAM) are in earlier stages of pilot or production ramps. Technologies such as carbon nanotube RAM (NRAM) are still primarily laboratory demonstrations.

The move to emerging technologies is not governed simply by technical issues. Intel's recent foray into the emerging memory business with its Optane brand of PCM "3D XPoint" memory has proven that the economies of scale play a role in a new technology's adoption that cannot be ignored.

This report discusses the leading solid-state memory and storage technologies shown in Figure 2.

**Figure 2. Solid State Memory/Storage Technologies**



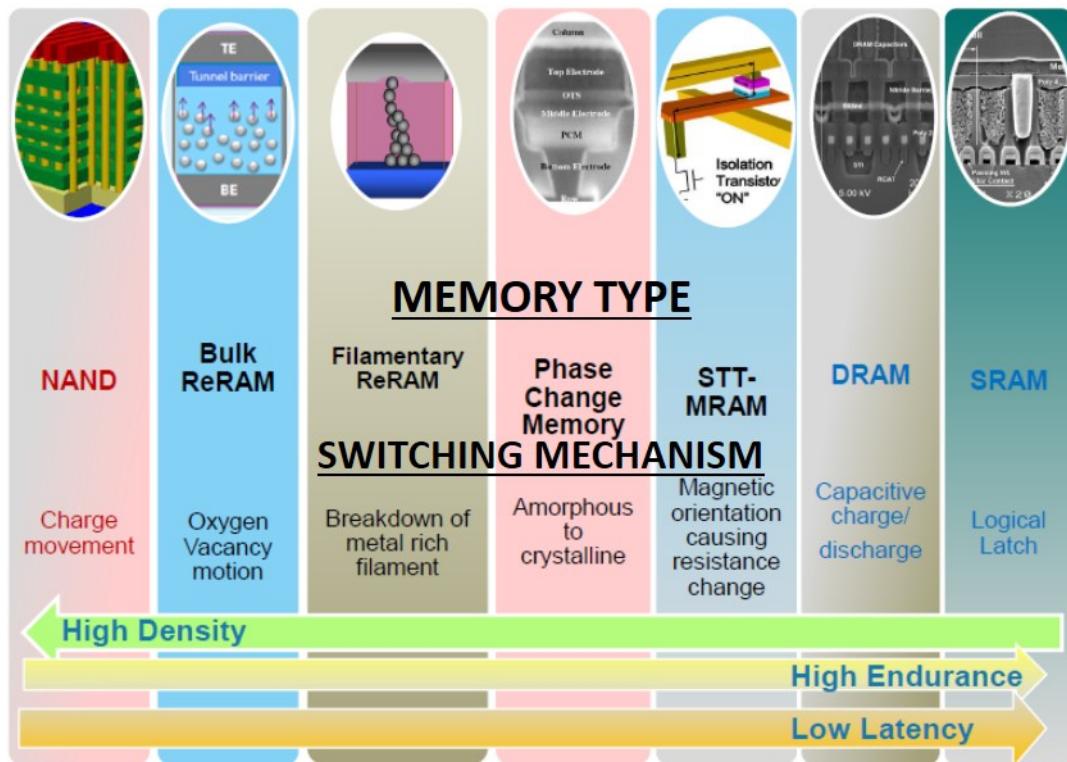
Source: Objective Analysis, 2024

The following emerging memory technologies are discussed in this report:

1. MRAM: Memories that use a magnetic effect
2. PCM: Memories based on phase changes through thermal effects
3. ReRAM: Memories that use ionic effects
4. FRAM: Electric field driven memories
5. New nonvolatile technologies such as Carbon Nanotube memories

The chart of Figure 3 provides an elementary overview of the first three of these technologies against established memory technologies: NAND flash, DRAM, and SRAM. This report will study all of the technologies mentioned above in considerable depth.

**Figure 3. Rough Comparison of Established and Emerging Memory Types**



This report addresses the characteristics of each nonvolatile technology from the following properties:

1. Compatibility with CMOS process and structure
2. Present commercial state of the technology
3. Reliability and/or endurance
4. Cost
5. Density
6. Performance
7. Ultimate limits

Two fundamental application types of emerging memories are examined in this report. The first is a standalone memory chip. Flash memory chips are an example of such a technology, as are DRAM chips. The second is adding an emerging memory within a logic chip like a microcontroller, ASIC, or SoC (system-on-a-Chip). These are often called embedded applications.

Note that the use of NAND flash memory as an embedded memory within a logic chip necessitates a significant variation to a standard CMOS process, which can multiply its cost. As a consequence, NAND flash is not used for internal memories in logic devices. NOR flash memory can be compatible with CMOS for an on-chip embedded memory. Similarly, DRAM is far less commonly found embedded in logic than is SRAM, its logic-friendly counterpart.

The report provides some details on the manufacture of MRAM products which are ramping up in volume to compete with SRAM, NOR and DRAM as a nonvolatile microprocessor memory. We will also point out what drives memory adoption and discuss why one memory can come to displace another.

The report then presents the Coughlin Associates analysis of MRAM production tool technologies and demand for these tools under a variety of scenarios, and the characteristics of capital equipment used for MRAM manufacturing. This demand estimate is based on the best-case of the above scenarios for MRAM market acceptance. We use this to project the capital equipment demand to produce MRAM from 2023-2034. We also discuss the implications for other nonvolatile technologies such as FRAM and ReRAM.

The report finishes with a listing of over 100 companies involved in various emerging memory technology development, production, and capital equipment.

The report presents data collected through careful interviews participants on all sides of the emerging memory market: Developers, vendors, licensors and licensees, tool makers, foundries, etc. Data was collected by Coughlin Associates and Objective Analysis via field interviews and at trade conferences and seminars. Other historical data was gathered from a wide variety of sources by the authors. Forecast data has been derived from primary and secondary sources, along with Objective Analysis' highly-regarded trend analysis of memory chip pricing and supply/demand dynamics. Capital spending reported here is an estimate since this is an emerging market. Conference attendance and extensive reading of widespread sources provided insight in technical areas. In certain cases, analyst judgment was called upon to expand upon the data that was available through these sources.

During reviews we were directed to lectures, interviews, and articles to obtain information concerning forecasts, expected technology directions, and future requirements. The authors wish to express our thanks to all colleagues who contributed their knowledge and insights to us as a valuable service to the storage and memory industry.

Not all of the detailed data that were gathered were included. As usual, if further questions or additional information is required, please contact the authors. The authors are also available to provide or develop additional information, on a project basis, (with due regard for the confidentiality of our sources.)

# AUTHORS

## *Tom Coughlin*

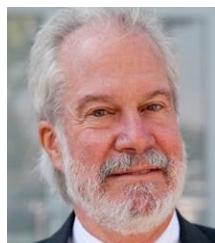


Tom Coughlin has worked for over 40 years in the data storage industry and is President of Coughlin Associates, Inc. He has over 800 publications and six patents and is a frequent public speaker on storage and memory topics. Tom is active with the IEEE, SMPTE, SNIA, and other professional organizations. Dr. Coughlin is an IEEE Fellow and HKN member. He is co-chair of the iNEMI Mass Storage Technical Working Group, Education Chair for SNIA CSMI, Past-President of IEEE-USA and a board member of the IEEE Consultants Network of Silicon Valley. Tom is the 2024 IEEE President.

His publications include the *Digital Storage Technology Newsletter*, *Media and Entertainment Storage Report*, and *The Emerging Memory Storage Report*. Tom is the author of *Digital Storage in Consumer Electronics: The Essential Guide*, now in its second edition with Springer. He has a regular Forbes.com blog called *Storage Bytes* and had a long running regular digital storage column for the *IEEE Consumer Electronics Magazine*. Tom is currently editing a column on digital storage and memory for the *IEEE Computer Magazine*.

He was the founder and organizer of the *Storage Visions Conferences* as well as the *Creative Storage Conferences*. He was general Chairman of the annual Flash Memory Summit for 10 years and was the program chair for 2 years. Coughlin Associates provides market and technology analysis as well as data storage technical and market consulting. For more information go to [www.TomCoughlin.com](http://www.TomCoughlin.com)

## *Jim Handy*



Jim Handy, a widely recognized semiconductor analyst, comes to Objective Analysis with over 30 years in the electronics industry including over 20 years as an industry analyst for Dataquest (now Gartner), Semico Research, and Objective Analysis. His background includes marketing and design positions at market-leading suppliers including Intel, National Semiconductor, and Infineon.

Mr. Handy is a member of the Storage Networking Industry Association (SNIA) Compute, Memory, and Storage Initiative (SSSI). He is also a Leader in the GLG Councils of Advisors, and serves on the Advisory Boards of the Flash Memory Summit. He has served as a member of the Mass Storage Technical Working Group of the International Electronics Manufacturing Initiative (iNEMI). He is the author of three blogs covering memory chips ([www.TheMemoryGuy.com](http://www.TheMemoryGuy.com)), SSDs ([www.TheSSDguy.com](http://www.TheSSDguy.com)), and semiconductors for the investor ([www.Smartkarma.com](http://www.Smartkarma.com) and formerly [blogs.Forbes.com/JimHandy](http://blogs.Forbes.com/JimHandy)). He contributes from time to time to a number of other blogs and professional journals.

A frequent presenter at trade shows, Mr. Handy is known for his widespread industry presence and volume of publication. He has written hundreds of articles for trade journals, Dataquest, Semico, and others, and is frequently interviewed and quoted in the electronics trade press and other media.

Mr. Handy has a strong technical leaning, with a Bachelor's degree in Electrical Engineering from Georgia Tech, and is a patent holder in the field of cache memory design. He is the author of ***The Cache Memory Book*** (Harcourt Brace, 1993), the leading reference in the field. Handy also holds an MBA degree from the University of Phoenix. He has performed rigorous technical analysis on the economics of memory manufacturing and sales, discrediting some widely held theories while unveiling other true motivators of market behavior.

Mr. Handy may be contacted at [Jim.Handy@Objective-Analysis.com](mailto:Jim.Handy@Objective-Analysis.com), or by telephone at +1 (408) 356-2549.